

ABSTRACT

The present invention describes an apparatus comprising a mask; a pellicle spacer, the pellicle spacer attached to the mask; and an electrostatic pellicle system, the electrostatic pellicle system attached to the pellicle spacer.

The present invention further describes a method of keeping contaminants away from a vicinity of a mask during exposure, the contaminants including an uncharged or neutral particle, a positively-charged particle, or a negatively-charged particle, comprising: inducing a positive or negative charge on the uncharged or neutral particle; attracting the positively-charged particle with a negatively-charged electric field; and attracting the negatively-charged particle with a positively-charged electric field.